

PATENT APPLICATION

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of

Takahiro TAMURA

Divisional Application of
Appln. No. 09/374,112

Group Art Unit: Not Assigned

Confirmation No.: Not Assigned

Examiner: Not Assigned

Filed: June 6, 2001

For: PLASMA CLEANING METHOD AND PLACEMENT AREA PROTECTOR USED IN
THE METHOD



**INFORMATION DISCLOSURE STATEMENT
UNDER 37 CFR §§ 1.97 and 1.98**

Commissioner for Patents
Washington, D.C. 20231

Sir:

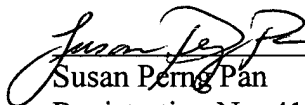
In accordance with the duty of disclosure under 37 CFR §1.56, Applicant hereby notifies the U.S. Patent and Trademark Office of the documents which are listed on the attached PTO-1449 form which are all the references of record in parent application No. 09/374,112. Applicant is not submitting duplicate copies of these references but requests that they be listed on the face of any patent granted on the above application. (See 37 CFR §1.98(d)) Copies of any cited copending applications, if not previously submitted, are being submitted herewith.

INFORMATION DISCLOSURE STATEMENT
Divisional of
U.S. Appln. 09/374,112

The submission of the listed documents is not intended as an admission that any such document constitutes prior art against the claims of the present application. Applicant does not waive any right to take any action that would be appropriate to antedate or otherwise remove any listed document as a competent reference against the claims of the present application.

Respectfully submitted,

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Form PTO-1449 (Rev. 2-32)		U.S. Department of Commerce Patent & Trademark Office		Atty. Docket No. Q64222		Serial No.: Division of U.S. Appn. 09/374,112 Confirmation No.: Not Assigned	
INFORMATION DISCLOSURE STATEMENT (Use several sheets if necessary)				Applicant: TAMURA, TAKAHIRO			
				Filing Date: June 6, 2001		Group: Not Assigned	
U.S. PATENT DOCUMENTS							
Examiner Initial		Document Number	Date	Name	Class	Sub-Class	Filing Date (if appropriate)
		4,340,456	07/1982	Robinson et al.			
		4,350,578	09/1982	Frieser et al.			
		4,528,438	07/1985	Poulsen et al.			
		5,259,888	11/1993	McCoy			
		5,314,509	05/1994	Kato et al.			
		5,269,881	12/1993	Sekiya et al.			
		5,602,061	02/1997	Fujimaki			
		5,346,578	09/1994	Benzing et al.			
		5,514,246	05/1996	Blalock			
		5,522,936	06/1996	Tamura			
		5,240,555	08/1993	Kilburm			
FOREIGN PATENT DOCUMENTS							
		Document	Date	Country	Class	Sub-class	Translation Yes/No
		JP Hei 5-55184	03/1993	Japan			
OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)							
		Grill, "Cold Plasma in Materials Fabrication," IEE Press, pages 99-101 (1994).					
		English language Abstract of Japanese Hei 5-55184.					
		Sze, "Semiconductor Devices," Wiley & Sons, pp. 341-380 (1985)					
		Pierson, "Handbook of Chemical Vapor Deposition (DVD)," Noyes Publications, pp. 231-234 and 278-282 (1982).					
		Hawkey's Chemical Dictionary, pp. 985, 986 and 1035.					
		Sherman, "Chemical Vapor Deposition for Microelectronics," Noyes Publication, pp. 66-77 and 131-136 (1987).					
		Dictionary of Science and Technology, W & R Chambers, pp. 495, 964, 1071 and 1254. (1974)					
EXAMINER:				DATE CONSIDERED:			
EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication.							